Scanning Tunneling Microscopy and Spectroscopy of Wet-Chemically Prepared Chlorinated Si(111) Surfaces

Supporting Information

Peigen Cao, Hongbin Yu[1], James R Heath[*]

Division of Chemistry and Chemical Engineering, Noyes Laboratory, 127-72

Kavli Nanoscience Institute

California Institute of Technology

Pasadena, California 91125

[1]*Current Address:* *Department of Electrical Engineering*
ERC 159, Mail Code 5706
Arizona State University
Tempe, AZ 85287-5706

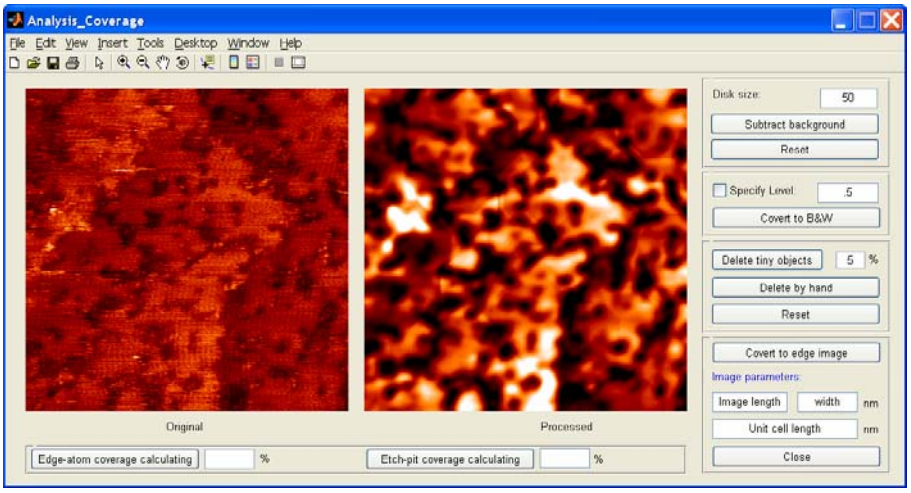
* Corresponding author:

heath@caltech.edu

Supporting Information

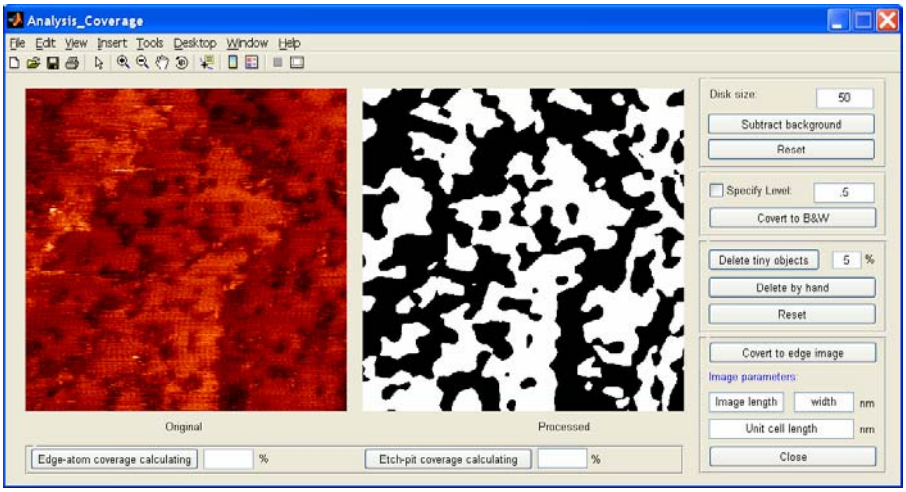
Etch-pit and edge-atom coverage calculation steps: (An approximate method)

1. Average and background subtraction;

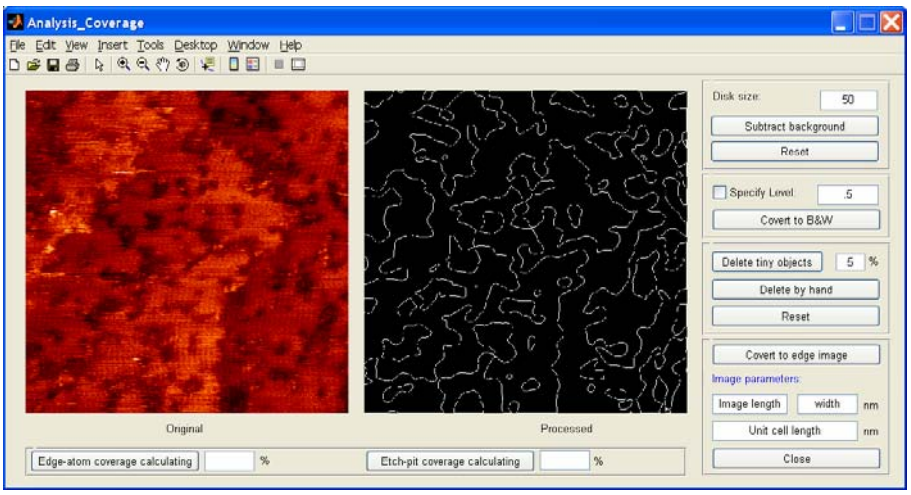


Note: different average level would lead to an error in the final result.

2. Converting to B&W images;



3. Converting to edge images;



4. Calculating the results;